

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION  
METHOD OF PHOTOMASK, AND  
FABRICATION METHOD OF  
SEMICONDUCTOR INTEGRATED  
CIRCUIT



Group Art Unit: 1756

Examiner: S. Mohamedulla

PETITION FOR EXTENSION OF TIME

Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

The following extension of time is requested to the Official Action dated May 24, 2000:  
one month to September 24, 2000; the extension fee is:

☐ \$55.00 (215) ☒ \$110.00 (115).

☐ The shortened statutory period has been reset by an Advisory Action dated

☒ An extension fee in the amount of \$ 110.00 is enclosed.

☐ Charge \$ \_\_\_\_\_ to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R.  
§§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to  
Deposit Account No. 02-4800. This paper is submitted in duplicate.

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

By: 

Ellen Marcie Emas  
Registration No. 32,131

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Date: September 22, 2000